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Group Art Unit: 1742

Attorney
Docket: 27054


For: Texturing A Semiconductor Material ...

INFORMATION DISCLOSURE STATEMENT

Sir:

Enclosed is a PTO Form 1449 which lists citations which may be material to the patentability and examination of the above identified application. Also enclosed are copies of the references cited. These are submitted in compliance with the duty of disclosure defined in 37 CFR 1.56. The Examiner is requested to make these citations of official record in this application.

This Information Disclosure Statement under 37 CFR 1.56 is not to be construed as a representation that a search has been made, that additional matter which is material to the examination of this application does not exist, or that any or more of these citations constitutes prior art.

Respectfully submitted,

 Sol Sheinbein
 Registration No. 25,457

Date: October 28, 2004

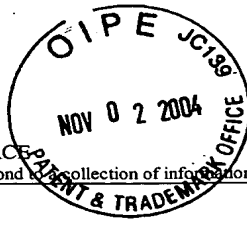
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PTO/SB/08A (10-96)



INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Complete if Known

Application Number	10/750,969
Filing Date	01/05/2004
First Named Inventor	Ein-Eli
Group Art Unit	1742
Examiner Name	

Sheet	1	Of	2	Attorney Docket Number	27054
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U.S. PATENT DOCUMENTS

Examiners Initials	Cite No. ¹	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD- YYYY	Pages, columns, lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code ² (if known)			
		6,340,640		Nishimoto et al	01-22-2002	
		6,197,611		Nishimoto	03-06-2001	
		5,990,002		Niroomand et a ;	11-23-1999	
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		6,521,118		Starosvetsky et al	02-18-2003	

FOREIGN PATENT DOCUMENTS

Examiners Initials	Cite No. ¹	Foreign Patent Documents			Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD- YYYY	Pages, columns, lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
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¹ Unique citation designation number. ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

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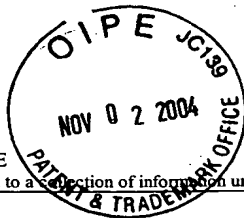
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PTO/SB/08A (10-96)



Substitute for form 1449A/PTO

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Complete if Known

Application Number 10/750,969

Filing Date 01/05/2004

First Named Inventor Ein-Eli

Group Art Unit 1742

Examiner Name

Sheet 2 Of 2 Attorney Docket Number 27054

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
		Ein-Eli et al, "Silicon Texturing Under Negative Potential Dissolution (NPD)", <i>Int. Soc. Electrochemistry</i> , Ann. Mtg., Thessaloniki, 19-24-Sept., 2004	
		Ein-Eli et al, "Silicon Texturing In Alkaline Media Conducted Under Extreme Negative Potentials", <i>Electrochem. & Solid State Letters</i> , 6(3):C47-C50, 2003	
		Starosvetsky et al, "Environmentally Friendly, Fast Electrochemical Etching of Silicon", <i>Electrochemical Society Proceedings</i> , Proceedings Vol. 2002-14, pp 286-299	
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		Sidell et al, "Anisotropic Etchings of Crystalline Silicon in Alkaline Solutions", <i>J. Electrochem Soc.</i> , 137(11): 3612-3626, 1990	
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		Vu et al, "Surface Characteristics of (100) Silicon Anisotropically Etched in Aqueous KOH", <i>J. Electrochem Soc.</i> , 143(4): 1372-1375, 1996	
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		Glembocki et al, "Bias-Dependent Etching of Silicon in Aqueous KOH", <i>J. Electrochem Soc.</i> , 132(1): 145-151, 1985	
		Tellier et al, "Anisotropic Etching of Silicon Crystals in KOH Solution", <i>J. Material Science</i> , 29:5953-5971, 1994	
		Green et al, "45% Efficient Silicon Photovoltaic Cell Under Monochromatic Light", <i>IEEE Electron Device Letters</i> , 13(6):317,318, 1992	
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		Wovte et al, "Grid-Connected Photovoltaic Systems", <i>International conference Power Generation and sustainable development (AIM)</i> , Liege, Belgium, October 8-9, 2001; pp. 233-238.	
		Nijs et al, "Crystalline Silicon Solar Cells Technology for Today and Tomorrow », Proc. Of the 16 th European Photovoltaic Solar Energy Conference, Glasgow, 2000	
		Ein-Eli et al, Suppresion of Zinc-Anode Corrosion in Alkaline Solutions with the Use of Organic Inhibitors", 202 nd Meeting of the Electrochemical Society, Salt Lake City, Utah, 200s, Abstarct 344	
		Sato et al, "Roughening of Single-Crystal Silicon Surface Etched by KOH Water Solution", <i>Sensors and Actuators</i> , 73:122-130, 1999	
Examiner Signature		Date Considered	

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